Form PTO 1449 (Modified)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY DOCKET NO.	SERIAL NO.
		244838US2S	New Application
LIST OF REFERENCES CITED BY APPLICANT		APPLICANT	
		Takashi YAMADA, et al.	
		FILING DATE	GROUP
		Herewith	

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA	6,531,754	03/11/03	Hajime NAGANO, et al.			
	AB	6,630,714	10/07/03	Tsutomu SATO, et al.			
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES	TRANSLATION NO
	AM	10-303385	11/13/98	Japan		x
	AN	8-316431	11/29/96	Japan		x
	AO	7-106434	04/21/95	Japan		x
	AP	11-238860	08/31/99	Japan		x
	AQ	2000-91534	03/31/00	Japan		x
	AR	2000-243944	09/08/00	Japan		x
	AS	8-17694	01/19/96	Japan		x
	AT	11-17001	01/22/99	Japan		x

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)

	AU	Robert HANNON, et al., "0.25 μm Merged Bulk DRAM and SOI Logic using Patterned SOI", SYMPOSIUM ON VLSI TECHNOLOGY DIGEST OF TECHNICAL PAPERS, 2000, pgs. 66-67
	AV	H. L. HO, et al., "A 0.13 μm High-Performance SOI Logic Technology with Embedded DRAM for System-On-A-Chip Application", IEDM TECH. DIG., 2001, pgs. 503-506
	AW	T. YAMADA, et al., "An Embedded DRAM Technology on SOI/Bulk Hybrid Substrate Formed with SEG Process for High-End SOC Application", SYMPOSIUM ON VLSI TECHNOLOGY DIGEST OF TECHNICAL PAPERS, 2002, pgs. 112-113
	AX	Hajime NAGANO, et al., "SOI/Bulk Hybrid Wafer Process Using SEG (Selective Epitaxial Growth) Technique for High-End SoC Applications", EXTENDED ABSTRACTS OF THE 2002 INTERNATIONAL CONFERENCE ON SOLID STATE DEVICES AND MATERIALS, 2002, pgs. 442-443
	AY	Takashi YAMADA, et al., "An Embedded DRAM Technology in SOI for High-End SoC Application", SEMI TECHNOLOGY SYMPOSIUM, 2002, pgs. 2-39-2-44 (with English Abstract)
	AZ	

☐ Additional References sheet(s) attached

Examiner

Date Considered 1-18-05

*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.